2012 International Symposium on Dry Process

Program

Thursday, November 15, 2012

Opening Remarks (9:30–9:40) H. Kokura (Fujitsu Semiconductor Ltd.)

Best/Young Award Ceremony (9:40–9:50) Presenter: M. Izawa (Hitachi High-technologies Corp.)

Nishizawa Award Lectures **9:50–10:50**

Chairperson: T. Ichiki (Univ. of Tokyo)

H. H. Sawin (Massachusetts Institute of Technology) **9:50–10:20**

R. A. Gottscho (Lam Research Corp.) **10:20–10:50**

Break (10:50–11:10)

Session A Surface Reaction (11:10–12:30)

Chairpersons: K. Nojiri (Lam Research Corp.), K. Karahashi (Osaka Univ.)

Lunch (12:30–13:30)

Session B <Arranged session> Plasma Biological Treatment and Medicine (13:30–15:10)

Chairpersons: M. Shiratani (Kyushu Univ.), M. Nakatani (Panasonic Corp.)

Break (15:10–15:30)

Poster Session (10:50–12:30)

Chairpersons: K. Kurihara (Toshiba Corp.), K. Nakamura (Mitsubishi Corp.)

Surface Reaction and Etching Technology

Plasma Generation, Diagnostics and Monitoring Technology

Modeling and Simulation

CVD/Sputter Deposition

Plasma Processes for 3D Device, FPD, Photovoltaic Devices

Session H Plasma Damage (16:50–17:50)

Chairpersons: H. Toyoda (Nagoya Univ.), N. Negishi (Hitachi Ltd.)

Closing Remarks (17:50–18:00)

N. Negishi (Hitachi, Ltd.)